# Non-equilibrium materials by fs-laser texturing and hyperdoping of silicon



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#### and also....

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irradiate with 100-fs 10 kJ/m<sup>2</sup> pulses





absorptance 
$$(1 - R_{int} - T_{int})$$



absorptance 
$$(1 - R_{int} - T_{int})$$





absorptance 
$$(1 - R_{int} - T_{int})$$



absorptance 
$$(1 - R_{int} - T_{int})$$



absorptance 
$$(1 - R_{int} - T_{int})$$



laser treatment causes:

- surface structuring
- inclusion of dopants

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SiOnyx

basic physics of hyperdoped semiconductors

how do structures form?



process of hyperdoping?





# electronic and optical properties?











## conditions to produce texturing?





#### heavy texturing





























































fewer pulses required to initiate & grow texture

at higher fluence








Smith, Sher, Franta, et al., J. Appl. Phys. 112 (2012)







































#### raster scanning samples





#### raster scanning samples

























#### What we learned

- texture onset depends on peak fluence
- texture onset does not depend on atmosphere
- quantitative agreement standing/scanning texturing





110 pulses, 20 Torr N<sub>2</sub> gas, 1.5 kJ/m<sup>2</sup>





110 pulses, 20 Torr N<sub>2</sub> gas, 1.5 kJ/m<sup>2</sup>





140 pulses, 760 Torr air, 1.5 kJ/m<sup>2</sup>





140 pulses, 760 Torr air, 1.5 kJ/m<sup>2</sup>





110 pulses, 20 (left)/760 (right) Torr N<sub>2</sub> gas, 1.5 kJ/m<sup>2</sup>



#### Questions

- What determines initial, random surface modification?
- What is role of surface plasmon polaritons?
- What is mechanism behind gas pressure effect?
- How can process be time resolved?























structuring



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fs pump-probe reflectometry

# melt velocity 30 km/s (athermal)

melt duration 1–10 ns

resolidification velocity 10–16 m/s





# diffusion model simulation







## diffusion model simulation







# diffusion model simulation







## What we learned

- melting via ultrafast lattice destabilization (athermal)
- resolidification velocity in range of critical velocity for amorphization (15 m/s)
- resolidification can be controlled by fluence (high fluence yields lower velocity)
- dopant profile can be described by classical diffusion
- dopant profile can be controlled and flattened













# structuring



#### properties 3

itionally, we

suggest that it is a classic impurity-driven Mott transition. DOI: 10.1103/PhysRevLett.108.026401 Of all the experimentally measurable physical properties of materials, electronic conductivity exhibits the largest variation, spanning a factor of 10<sup>31</sup> from the best metals to variation, spanning a factor of 10 from the last century, the the strongest insulators [1]. Over the last century, the puzzle of why some materials are conductors and others PULLIC OF WHY SOURCE MACHAIS are COMMINING the transformation insulators, and the mechanisms underlying the transformation of the tr tion from one to the other, have been carefully scrutinized; uon nom one to the other, have occur carefully security and a long yet even after such a vast body of research over such a long yer oven and such a vase usery or research over such a roug period, the subject remains the object of controversy. In 1956 Nett introduced a model for the involution to motel 1956, Mott introduced a model for the insulator-to-metal transition (IMT) in doped semiconductors, in which long ranged electron correlations are the driving force [2]. Hyperdoping (doping beyond the solubility limit) creates a new materials playground to explore defect-mediated Ertekin et al., Phys. Rev. 6 in the solution of the solution of the first and electron to the solution of the

implantation followed by nanosecond pulsed-laser melting (PLM) and rapid resolidification. The PLM process ena-(LLM) and rapid resolution and the LLM process one bles chalcogen doping with concentrations exceeding 1% atomic; such samples exhibit unexplained optical properawme, such samples commun uncorplamen optical photons ties including broad, featureless absorption of photons ues including vival, realulciess ausviption or provide [9]. with energy lower than the band gap of silicon [9]. with energy lower than the value gap of shifting were Silicon substrates (boron doped,  $\rho \approx 25 \ \Omega \text{ cm}$ ) were ion implanted with Se to nominal doces of  $3 \times 10^{15}$  and ion implanted with Se to nominal doses of  $3 \times 10^{15}$  and  $1 \times 10^{16}$  cm<sup>2</sup> using an ion been energy of 176 toty The Not implained with SC to noninnal access of  $3 \times 10^{-10}$ . The  $1 \times 10^{16}$  cm<sup>2</sup> using an ion beam energy of 176 keV. (a.t. implanted samples were exposed to four laser pulses (fluimplained samples were exposed to four laser pulses (nu-ences of 1.7, 1.7, 1.7 and 1.8 J cm<sup>-2</sup>). This fluence regimen results in a slightly shallower dopant profile, and higher up in a sugary sharpwer uppan provide and intervention than reported previously [18]. The Se concentration, than reported according to 20 pm rystalline, extends approximately 350 nm electrically isolated from the ction formed between measured

and Se dopants are well-established deep double donors in and be uppanes are wen-established user upune upper-silicon [3,14], the enhanced optical properties of hyper-Survey 12,1-17, we canance optical properties or hyper-doped silicon (in which these chalcogenic impurities are prosent at more menor concentrations) are not yet went understood. Further, unlike the prototypical system of phosphorus-doped silicon for which the INT has been extensively studied and characterized [15,16], there are very few studies of an IMT resulting from deep defects We prepared Se-doped silicon (Se:Si) samples using ion such as chalcogens [17].

PACS numbers: 71.30.+h, 61.72.sd, 73.61.Cw, 78.20.Bh silicon appears to justify such interest. While isolated S

Insulator-to-Metal Transition in Selenium-Hyperdoped Silicon: Observation and Origin Elif Ertekin,<sup>1,\*</sup> Mark T. Winkler,<sup>2,†</sup> Daniel Recht,<sup>3</sup> Aurore J. Said,<sup>3</sup> Michael J. Aziz,<sup>3</sup> Tonio Buonassisi,<sup>2</sup> and Jeffrey C. Grossman<sup>1,2,4</sup> Tonio Buonassisi,<sup>2</sup> and Jeffrey C. Grossman<sup>1,2,4</sup> Cambridge Massachusetts 02139, USA Massachusetts Institute of Technology, Cambridge Massachusetts 02139, USA <sup>2</sup>Department of Mechanical Engineering, Massachusetts Institute of Technology, Cambridge Massachusetts 02139, USA partment of Materials Science and Engineering, Massachusetts Institute of Technology, Cambridge Massachusetts 02139, USA <sup>2</sup>Department of Mechanical Engineering, Massachusetts Institute of Technology Massachusetts 02138, USA PRL 108, 026401 (2012) Hyperdoping has emerged as a promising method for designing semiconductors with unique optical and lectronic properties, although such properties currently lack a clear microscopic explanation. Hyperdoping nas emerged as a promising method for designing semiconductors with unique optical and electronic properties, although such properties currently lack a clear microscopic explanation. Combining computational and experimental evidence, we nrobe the origin of sub-band-gan ontical absorption electronic properties, although such properties currently lack a clear microscopic explanation. Combining computational and experimental evidence, we probe the origin of sub-band-gap optical absorption and metallicity in Se-hyperdoned Si. We show that sub-band-gap absorption arises from direct defect computational and experimental evidence, we probe the origin of sub-band-gap optical absorption and metallicity in Se-hyperdoped Si. We show that sub-band-gap absorption arises from direct defect to-conduction-band transitions rather than free carrier absorption. Density functional theory predicts and metallicity in Se-hyperdoped Si. We show that sub-band-gap absorption arises from direct detect-to-conduction-band transitions rather than free carrier absorption. Density functional theory predicts and Se-induced insulator-to-metal transition arises from merging of defect and conduction bands. to-conduction-band transitions rather than free carrier absorption. Density functional theory predicts the order and conduction bands, at a second insulator-to-metal transition arises from merging of defect and calculations confirm the experiment. Ouantum Monte Carlo calculations confirm the experiment. Se-induced insulator-to-metal transition arises from merging of detect and conduction bands, at a concentration in excellent agreement with experiment. Quantum Monte Carlo calculations accurately, and critical concentration, demonstrate that correlation is important to describing the transition accurately. concentration in excellent agreement with experiment. Quantum Monte Carlo calculations confirm the critical concentration, demonstrate that correlation is important to describing the transition accurately, and suggest that it is a classic impurity-driven Mott transition

13 JANUARY 2012

#### structuring 1





Ertekin et al., Phys. Rev. Lett. ed 108, e026401 (6 cm<sup>-3</sup>) and we to concentrations of concentrations of the frat (2012) raise of the frat (2012) and most resembles ally, we

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 $\approx 25 \Omega \text{ cm}$  $\log_{10^{15}}$  and

were

# carrier lifetime



Sher et al., Appl. Phys. Lett. (2014)





### absorption coefficient and mobility



Sher et al., Appl. Phys. Lett. (2014)





#### carrier transport



Sher et al., Appl. Phys. Lett. (2014)















Franta et al., Appl. Phys. Lett. 118 (2015)







Franta et al., Appl. Phys. Lett. 118 (2015)







Franta et al., Appl. Phys. Lett. 118 (2015)





What we learned

- carrier lifetime 1–100 ps
- lifetime decreases with increasing dopant concentration
- optical activity and be reversibly activated and deactivated
- dopant behavior depends on cooling rate







# **Work Supported**

#### **Publications**

- Franta, B. Fabrication techniques for femtosecond laser textured and hyperdoped silicon. Doctoral dissertation, Harvard University.
- Franta, B., D. Pastor, H. Gandhi., P. Rekemeyer., S. Grade ak, M. Aziz, E. Mazur . Increasing the crystallinity and optical absorptance of hyperdoped black silicon using nanosecond laser annealing. Journal of Applied Physics, 2015. 118, p. 225303.
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- Lin, Yu-Ting. 2014. Femtosecond-laser hyperdoping and texturing of silicon for photovoltaic applications. Doctoral dissertation, Harvard University.
- Smith, M., Sher, M.-J., Franta, B., Lin, Y.,-T., Mazur, E., Gradecak, S. Improving Dopant Incorporation During Femtosecond-Laser Doping of Si with a Se Thin-Film Dopant Precursor. Applied Physics A. 114, p. 1009-1016.

#### Patents/disclosures

- Aziz, M., Franta, B., Mazur, E, Pastor, D., US Patent Application 62/166,617
- Aziz, M., Franta, B., Mazur, E, Pastor, D., PCT/US 15/60385
- Mazur, E., Gandhi, H., ROI Oct 2014

### **Future work**

- time-resolved measurements of Si structures
- tomographic measurements of reactivated dopants
- intermediate band formation in Ge
- ultrafast laser texturing of Ge

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AFOSR

for more information and a copy of this presentation:

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